

Thermal modelling of smart power devices

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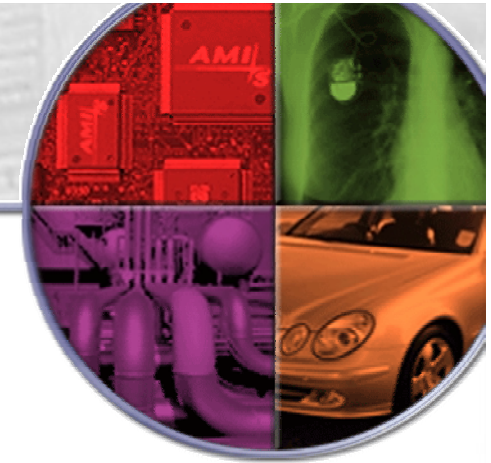


Thermal simulation tool



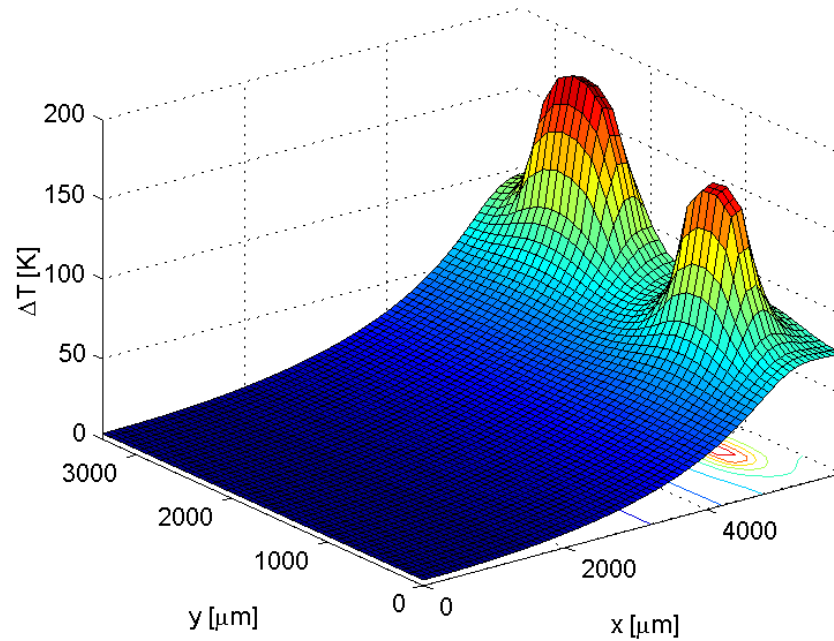
- **Thermal simulation tool developed in Matlab**
- **Analytical solution based on Green's functions**
- **Assumptions:**
 - Adiabatic top boundary, while other boundaries at infinity
 - Rectangular power sources
- **Adiabatic die edges: using method of images**
- **Calculation of $T(x,y,z,t)$:**
 - For any number of power sources
 - For any power function $P(t)$
- **Advantages:**
 - **Faster** than dedicated commercial software
 - Good **accuracy**
 - **Flexible** for designers

Simulations on smart-power IC

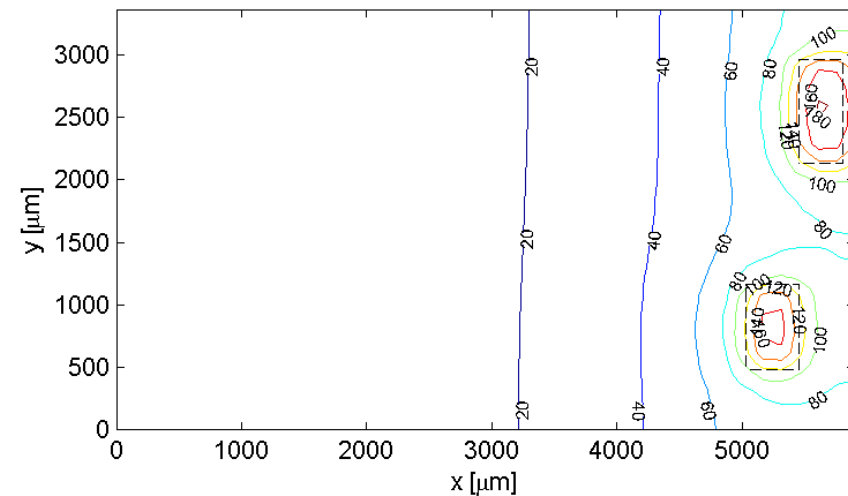


- **Example: 2 DMOS drivers inside H-bridge**
- **Power step function: 12.5 W per driver**

product IC temperature rise, $P_{\text{total}} = 25 \text{ W}$, $t = 100 \text{ ms}$



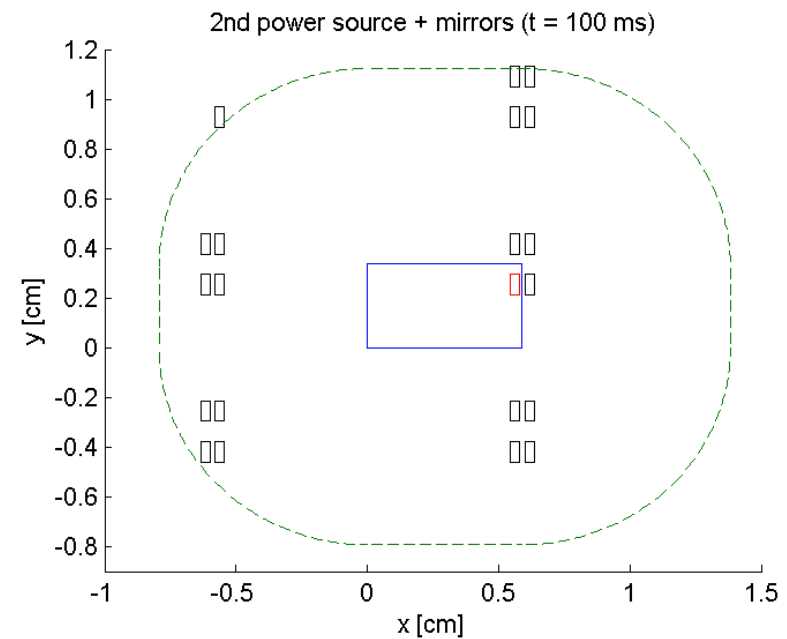
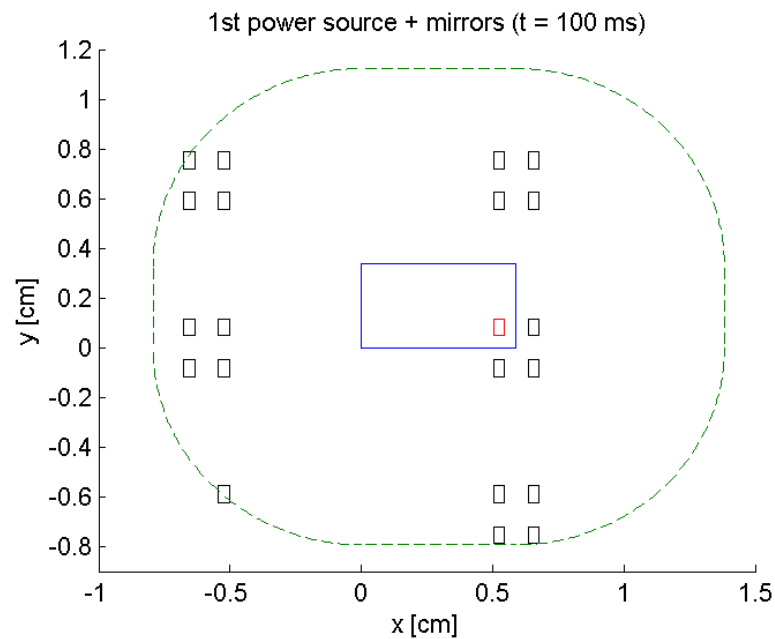
product IC temperature rise, $P_{\text{total}} = 25 \text{ W}$, $t = 100 \text{ ms}$



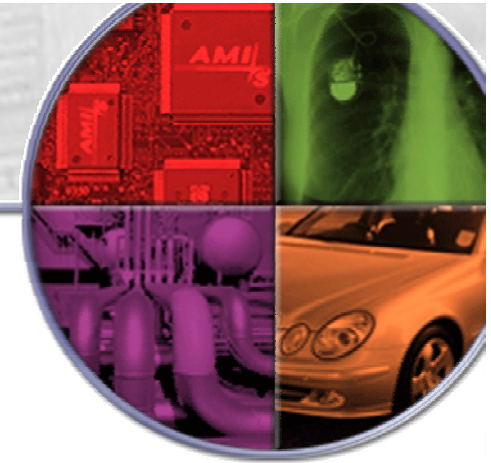
Method of images



- **Adiabatic die edges: introduce image sources**
- **Number of images limited by thermal diffusion boundary (grows with time)**

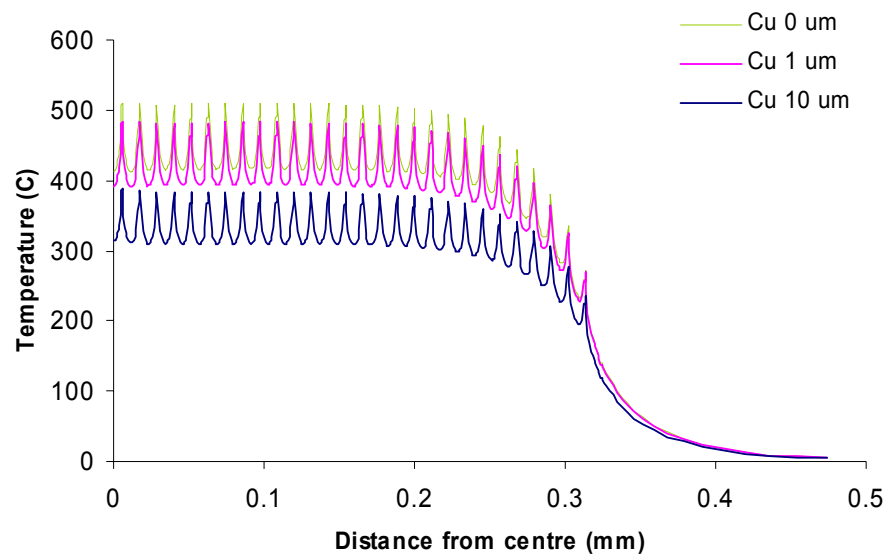


Comparison commercial software

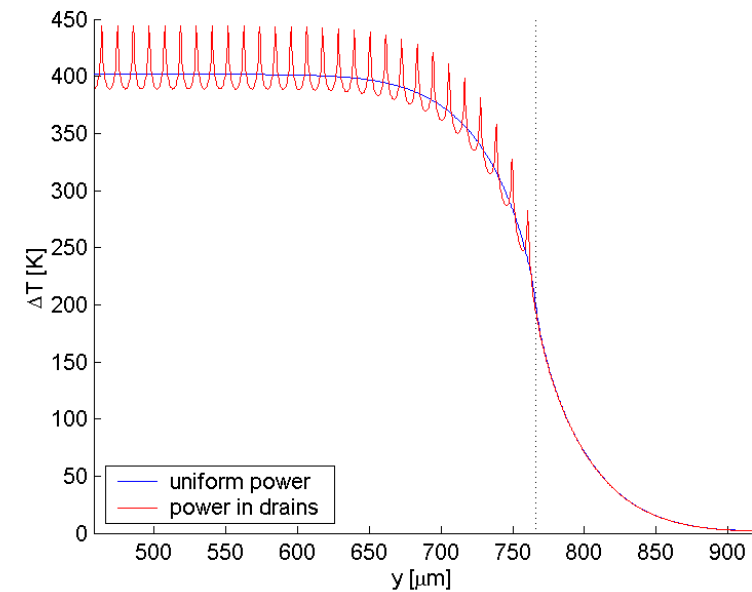


- Numerical simulations: **MSC.Marc** software
- Good **agreement** for small Cu thickness

commercial software



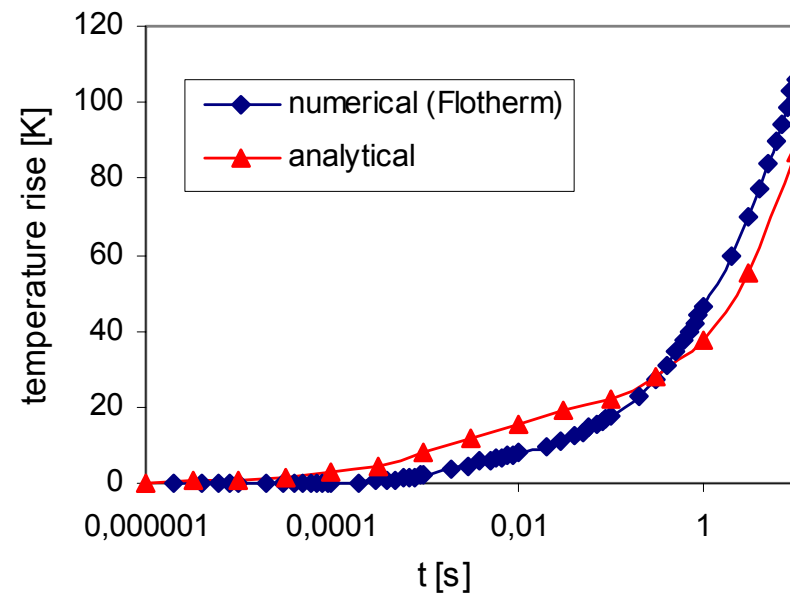
developed tool



Comparison commercial software



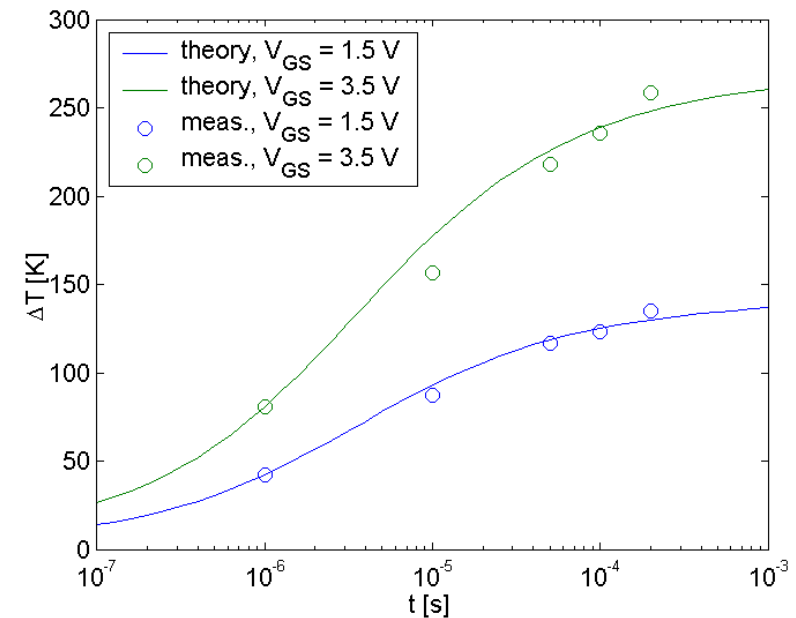
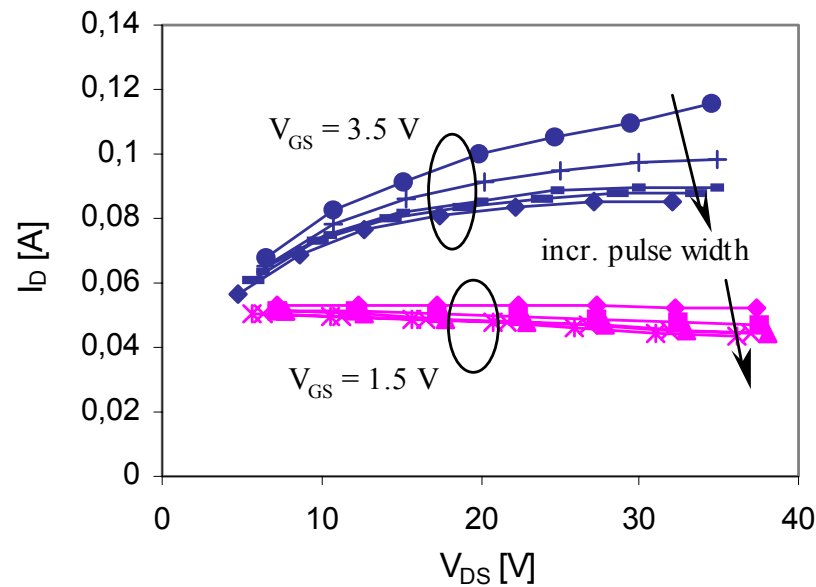
- Numerical simulations: Flotherm software
- Good **agreement** up to 10 s: much longer than typical diffusion time (~ 100 ms)



Pulsed measurements validation



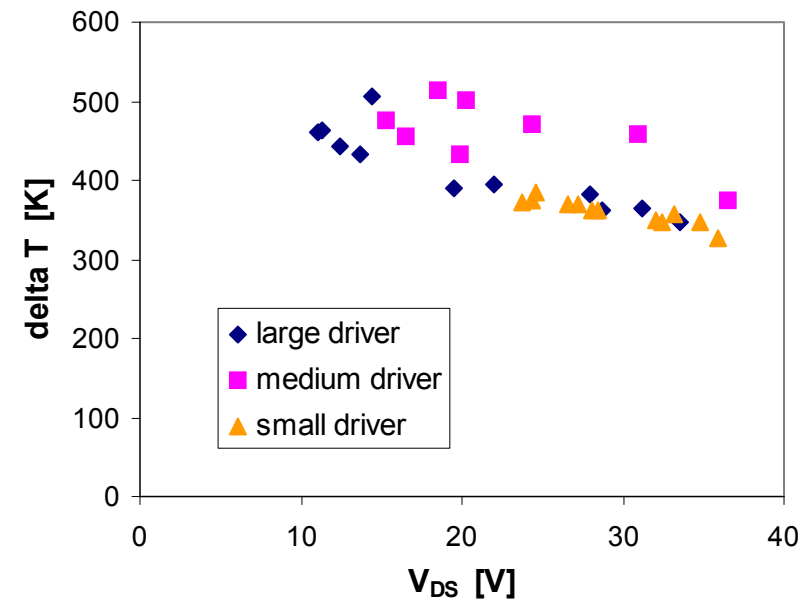
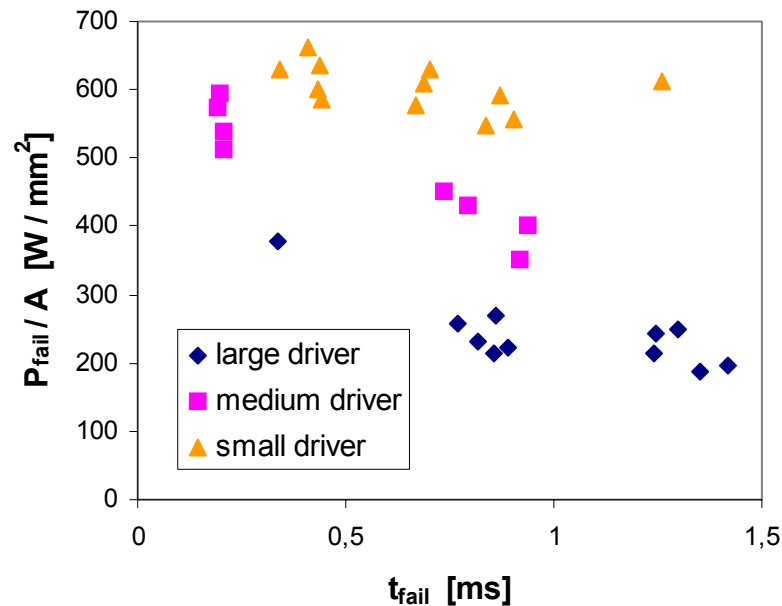
- **Mobility decrease model:** $I/I_0 = (T/T_0)^{-k}$
- **Current decrease used to predict temperature increase (using high-field k -value)**
- **Good agreement** if T_0 same as predicted by analytical model



Thermal failure prediction



- **Energy capability measurements:**
range of (V_{DS}, V_{GS}) -values \rightarrow range of (P_{fail}, t_{fail}) -values
- **Prediction of T_{fail} using tool:**
 - Low V_{DS} : **agreement** with TCAD simulations
 - High V_{DS} : earlier failure **explained** by impact-ionisation



Acknowledgements



- **Acknowledgements:**

P. Moens¹, E. Driessens², B. Elattari², G. Van den Bosch², R. Gillon¹, G. Groeseneken¹

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- **Project funding: IWT Project COMPOSE (Characterisation, Optimization and Modelling of Power Semiconductor Devices, project nr. 30042)**